L Number	Hits	Search Text	DB	Time stamp
1	2050	(gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:04
2	278	((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:06
3	160	(((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:06
4	103	((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:07
5	65	(((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:08

6	9	((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)) and 250/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:14
8	56	((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)) not (((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)) and 250/$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:14

11	43	(((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)) not ((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)) and 250/$.ccls.)) and chamber$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:15

13	43	(((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)) not (((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)) and 250/$.ccls.)) and chamber$1) and (vacuum with (chamber$1 or hous$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:19

14	13	(((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)) not (((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)) and 250/$.ccls.)) not (((((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1))) and vacuum) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4)) same ((irradiat$4 or radiat$4 or exposur$4) with (electron$1 adj beam) with (film$1 or substrate$1 or wafer$1)) same vacuum)) not (((((((gas$4 or outgas$4) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1)) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or creat$4 or collect$4)) same (irradiat$4 or radiat$4 or exposur$4) same (electron$1 near3 beam) same (film$1 or substrate$1 or wafer$1))) and (((gas$4 or outgas$4) with (releas$4 or produc$4 or	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:19
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